

## ABSTRACT OF THE DISCLOSURE

A semiconductor device manufacturing system for manufacturing a semiconductor device on a wafer, comprising: a first exposure apparatus for exposing the wafer using a light source while moving the wafer with a predetermined interval; and a second exposure apparatus for exposing the wafer by irradiating a plurality of electron beams on the wafer, the plurality of electron beams having an interval of substantially  $N$  times or  $1/N$  times, where  $N$  is a natural number, of the predetermined interval.

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